



IN THE UNITED STATES

PATENT AND TRADEMARK OFFICE

APPLICANTS: Yowjuang William Liu and Donald L. Wollesen

PRIOR APPLICATION:

SERIAL NO.: 09/052,057

FILING DATE: March 30, 1998

TITLE: Trenched Gate Non-Volatile Semiconductor Device With The Source/Drain Regions Spaced From the Trench by Sidewall Dopings

EXAMINER: H. Weiss

GROUP ART UNIT: 2814

ATTY. DKT. NO.: 2974

NEW ATTY. DKT. NO. 5251

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Assistant Commissioner For Patents, Washington, DC 20231, on the date printed below:

Dated: July 21, 2000

By: [Signature]

Trinidad Arriola Kern, Reg. No.: 44,012

BOX PATENT APPLICATION
ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

PRELIMINARY AMENDMENT

Sir:

Prior to Examination of the above-identified patent application, please amend the above-referenced application as set forth below.

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NOV 14, 2000
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